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APPLICATION N	iO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/604,533 07/29/2003		07/29/2003	Joachim Nuetzel	FIS920020132US1	1532
29371	7590	06/03/2005		EXAMINER	
	R COLBU		MITCHELL, JAMES M		
	FIELD, CT		ART UNIT	PAPER NUMBER	
				2813	
				DATE MAILED, 06/02/2004	-

Please find below and/or attached an Office communication concerning this application or proceeding.

			N			
		Application No.	Applicant(s)			
Office Action Summary		10/604,533	NUETZEL ET AL.			
		Examiner	Art Unit			
		James M. Mitchell	2813			
Period f	The MAILING DATE of this communication apor Reply	pears on the cover sheet with the c	orrespondence address			
THE - Exte after - If th - If NO - Failt Any	MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1. In SIX (6) MONTHS from the mailing date of this communication. In SIX (6) MONTHS from the mailing date of this communication. In SIX (6) MONTHS from the mailing date of this communication. In SIX (6) MONTHS from the mailing date of this communication. In SIX (6) MONTHS from the mailing date of the period for reply specified above, the maximum statutory period ure to reply within the set or extended period for reply will, by statut reply received by the Office later than three months after the mailing date of the period for reply will.	.136(a). In no event, however, may a reply be timoly within the statutory minimum of thirty (30) days I will apply and will expire SIX (6) MONTHS from the, cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status						
1)⊠	Responsive to communication(s) filed on 28 F	February 2005.				
		is action is non-final.				
3) Since this application is in condition for allowance except for formal matters, prosecution as to the m						
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposit	ion of Claims					
5)□ 6)⊠ 7)□	Claim(s) <u>1-15</u> is/are pending in the application 4a) Of the above claim(s) is/are withdra Claim(s) is/are allowed. Claim(s) <u>1-15</u> is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/o	awn from consideration.				
Applicat	ion Papers					
9)□	The specification is objected to by the Examin	er.				
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
	Applicant may not request that any objection to the	e drawing(s) be held in abeyance. See	e 37 CFR 1.85(a).			
	Replacement drawing sheet(s) including the correct	ction is required if the drawing(s) is obj	ected to. See 37 CFR 1.121(d).			
11)	The oath or declaration is objected to by the E	xaminer. Note the attached Office	Action or form PTO-152.			
Priority	under 35 U.S.C. § 119					
a)	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Bureasee the attached detailed Office action for a list	nts have been received. Its have been received in Applicationity documents have been received au (PCT Rule 17.2(a)).	on No ed in this National Stage			
Лись	*(a)					
Attachmen	ιτ(s) ce of References Cited (PTO-892)	4) Interview Summary	(PTO.413)			
2) Notic	e of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail Da	ite			
	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08 or No(s)/Mail Date) 5) Notice of Informal P 6) Other:	atent Application (PTO-152)			

Application/Control Number: 10/604,533

Art Unit: 2813

4

DETAILED ACTION

1. This office action is in response to the amendment filed February 28, 2005.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 3. Claims 1-5 and 6-14 are rejected under 35 U.S.C. 102(b) as being anticipated by Ning et al. (U.S. 2002/0098676).
- 4. Ning (Fig. 3-5; Par.0026-0027) discloses:
- (cl. 1, 10) a device and method for forming an interconnect structure in a magnetic random access memory (MRAM) device, the method comprising defining magnetic stack layer (218) on a lower metallization level (210), said magnetic stack layer including a non-ferromagnetic layer (216) disposed between a pair of ferromagnetic layers (218): defining a conductive hard mask (244) over said magnetic stack layer; and removing selected portions of said hardmask and said magnetic stack layer (Fig. 4-5), thereby creating an array (250) of magnetic tunnel junction stacks, MJT (Fig. 5), said stacks including remaining portions of said magnetic stack layer and said hardmask, wherein said hardmask forms a self-align contact between said magnetic stack layer and an upper metallization level (252) subsequently formed above said MTH stacks; (cl. 2, 3, 8, 11) depositing a cap layer (240) over said MTJ stacks and exposed portions or said lower-metallization level; depositing an interlevel dielectric (ILD) layer (220) over

Art Unit: 2813

said cap layer; and defining /via openings (250) for said upper metallization level in said ILD layer; wherein portions of said cap layer atop said MTJ stacks are used as an etch stop (Par. 0027);

- (cl. 4, 9,13) removing portions of said cap layer (Fig. 5) exposed by said upper metallization openings and said via openings; and filling said upper metallization openings and said via openings with a conductive material (252) by dual damascene (Par. 0042);
- (cl. 12) wherein there is a plurality via openings (Fig. 5);
- (cl. 5, 14) wherein said hardmask comprises a conductive material selected from the group of: tantalum, tungsten, titanium, tantalum nitride, tungsten nitride, titanium nitride and combinations comprising at least one of the foregoing (Par. 0027).
- 5. With respect to process limitation in claims 10-15, such as "created by removal of hard mask," the product in the product-by-process claim is the same as a product of the prior art. As such, "[E]ven though product-by-process claims are limited by and defined by the process, determination of patentability is based on the product itself. The patentability of a product does not depend on its method of production. If the product in the product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior product was made by a different process." In re Thorpe, 777 F.2d 695, 698, 227 USPQ 964, 966 (Fed. Cir. 1985)

Claim Rejections - 35 USC § 103

Application/Control Number: 10/604,533 Page 4

Art Unit: 2813

6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. Claims 5 and 15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ning et al. U.S. 2002/0098676).
- 8. Ning discloses the elements stated in paragraphs 4 and 5 of this office action and further disclosed that its hard mask may be of other materials (Par. 0027, 0031).
- 9. Ning does not expressly disclose the use of silicon nitride as its hardmask; however, use of silicon nitride would have been obvious since it has been held that to be within the general skill of a worker in the art to select known material on the basis of its suitability for intended use as a matter of obvious design choice. *In re Leshin*, 125 USPQ 416

Response to Arguments

10. Applicant's arguments with respect to claims have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

11. Any inquiry concerning this communication or earlier communications from the examiner should be directed to James M. Mitchell whose telephone number is (571) 272-1931. The examiner can normally be reached on M-F 8:00-4:00.

Art Unit: 2813

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on (571) 272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

CARL WHITEHEAD, JH.
SUPERVISORY PATENT EXAMINES:
TECHNOLOGY CENTER 2800

Page 5